

67,200-1145  
2002-1332

ABSTRACT OF THE DISCLOSURE

[0039] A method for exposing a blanket photoresist layer employs exposing a minimum of two non-overlapping die sub-patterns within a single die region of the blanket photoresist layer, each exposed while employing a minimum of two separate masks. The use of the multiple masks and multiple sub-patterns provides upon development a patterned photoresist layer with enhanced dimensional precision and uniformity.